

Roll No.

**Total No. of Pages : 02**

**Total No. of Questions : 08**

**M.Tech. (Emb Sys) (Sem.-3)**

## SENSOR TECHNOLOGY AND MEMS

**Subject Code : MTES-PE5B-18**

**M.Code : 76853**

**Date of Examination : 12-12-22**

**Time : 3 Hrs.**

**Max. Marks : 60**

**INSTRUCTIONS TO CANDIDATES :**

**1. Attempt any FIVE questions out of EIGHT questions.**

**2. Each question carries TWELVE marks.**

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|----|----|--|---------|
| 1. | a) | Draw the Primary and Secondary flats for n type {100} and p type {100} silicon wafer.  | 2       |
|    | b) | With suitable diagram, differentiate between sputtering and e-beam evaporation.  | 6       |
|    | c) | What do you mean by Etch Selectivity? Explain with example.  | 4       |
| 2. | a) | Explain the process of RF magnetron sputtering with the help of diagram.   | 6       |
|    | b) | Write the steps of silicon fusion bonding.   | 6       |
| 3. | a) | What are the three principal Silicon compound materials used in MEMS and Microsystems? Explain briefly about each of them.   | 1.5+4.5 |
|    | b) | Enlist all the basic steps in UV photolithography for pattern transfer (with the help of diagrams).  | 6       |
| 4. | a) | Enlist all methods by which dopants can be introduced into silicon. Explain two of them (with diagrams) which are used for locally varying the dopant concentration. | 6       |
|    | b) | Draw the schematic of MEMS accelerometer and describe its working and application.   | 6       |
| 5. | a) | What do you mean by pull-in phenomenon? Explain with the help of diagram. Also, derive the expression for pull-in.   | 6       |
|    | b) | Write the brief process (in steps) of modeling of MEMS device.   | 6       |

6. a) Describe various sensing and actuating mechanism (with one example for each) in MEMS. 6  
b) Write a short note on piezoresistors with one example 6
7. a) What are the applications of polymers in MEMS and explain methods to make polymers electrical conductive. 6  
b) Differentiate between bulk and surface micro machining. Explain the role of sacrificial layer in fabrication of MEMS devices. 6
8. State various deposition techniques. Explain in brief the technique of PVD for MEMS device Fabrication. Also define step coverage and shadowing. 12

**NOTE : Disclosure of Identity by writing Mobile No. or Making of passing request on any page of Answer Sheet will lead to UMC against the Student.**